

Lithography Solvent Bench

Operating Procedures LINK



Equipment Description:

The chemical bench has with two temperature-controlled tanks and one sink. The heated tanks contain Shipley 1165 Remover and are dedicated to removing photoresist. One tank is for wafers and the other is for photolithography masks. There are low-level sensors in each tank that when activated prevent heating of the solvent. The tank temperatures are controlled via a closed-loop control system with redundant over-temperature safety interlocks. The bench is also equipped with two solvent carboys with full-level sensors. The two tanks and the bench deck basin drain into the carboys.

<i>Materials Allowed</i>	<i>Materials Not Allowed</i>
1165 Remover	Acids
Acetone	Bases
Glass	Oxidizers
Isopropanol	Plastics
Metals	Polymers
Methanol	SU-8
Photoresists	
Quartz	
Silicon	
Silicon oxide	
Silicon nitride	